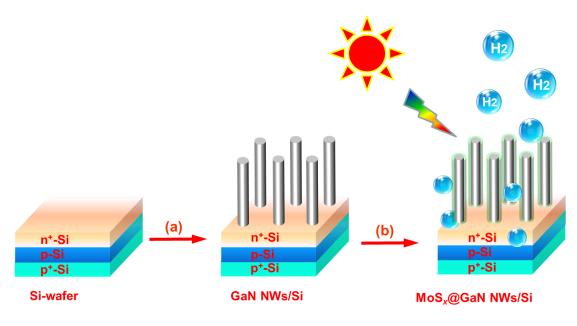
## Supplementary information

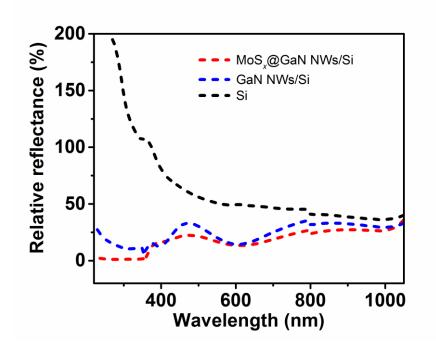
## Gallium nitride nanowire as a linker of molybdenum sulfides and silicon for photoelectrocatalytic water splitting

Zhou et al.

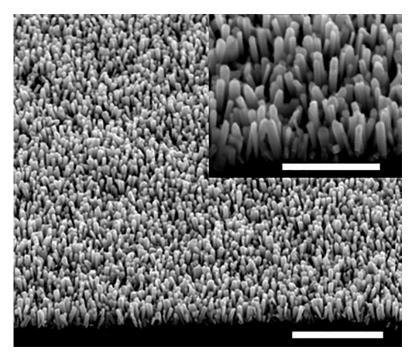


(a): Molecular beam epitaxy; (b): Electrodeposition

**Supplementary Figure 1** | Fabrication of shell-core  $MoS_x@GaN NWs/Si$  by molecular beam epitaxy and electrodeposition for solar water splitting to hydrogen.

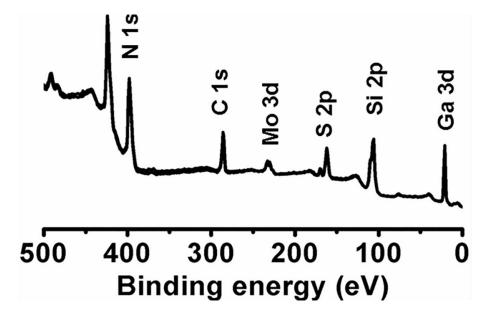


**Supplementary Figure 2** | UV-Vis relative reflectance spectra of Si, GaN NWs/Si, and  $MoS_x@GaN NWs/Si$  measured under identical conditions.

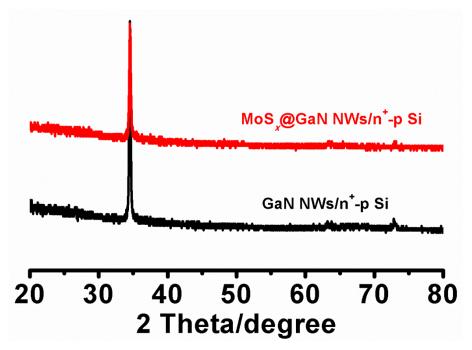


Supplementary Figure 3 | SEM image of GaN NWs/Si in the absence of  $MoS_x$ . Scale bar: 1  $\mu m$ ,

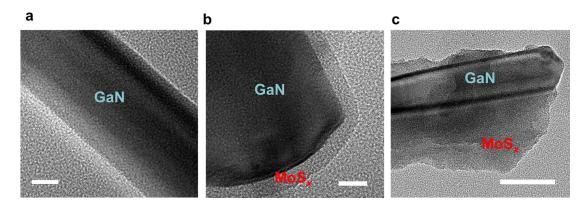
inset 500 nm.



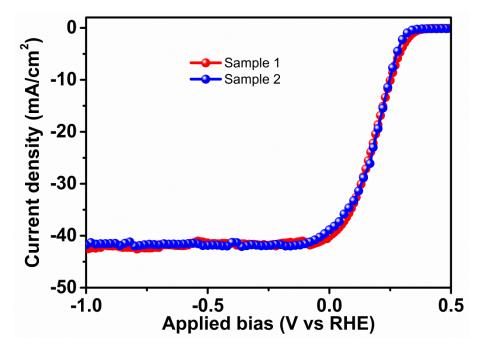
**Supplementary Figure 4** | X-ray photoelectron spectrum of  $MoS_x@GaN NWs/Si$ .



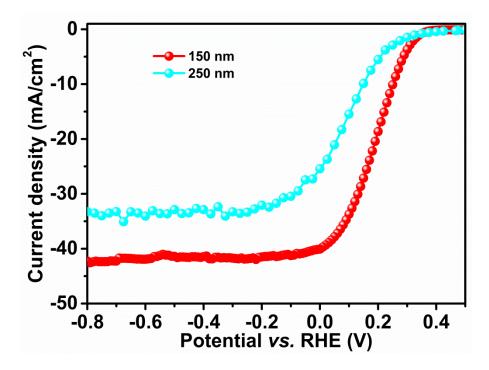
**Supplementary Figure 5** | X-ray diffraction spectral of GaN NWs/Si and  $MoS_x@GaN NWs/Si$ .



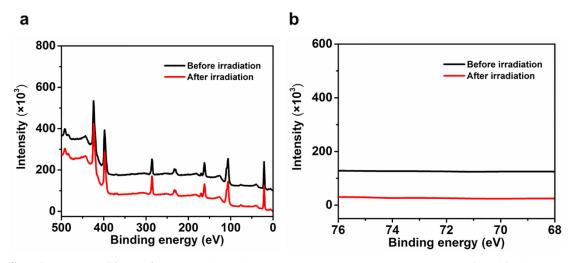
**Supplementary Figure 6** | TEM images of GaN NWs/Si deposited with various densities of  $MoS_x$ . **a** 0 µmol cm<sup>-2</sup>, **b** 0.73µmol cm<sup>-2</sup>, and **c** 1.72µmol cm<sup>-2</sup>. Scale bars: **a-b** 10 nm and **c** 50 nm



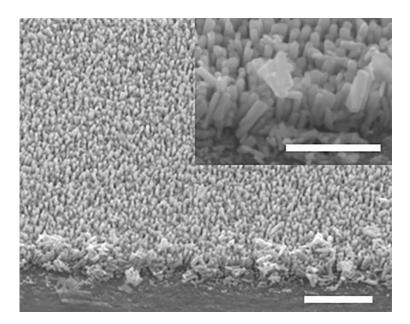
**Supplementary Figure 7** | The variation of PEC performance of  $MoS_x@GaN NWs/Si$  with 0.73  $\mu$ mol cm<sup>-2</sup> of  $MoS_x$  under standard one-sun illumination in 0.5 M H<sub>2</sub>SO<sub>4</sub>.



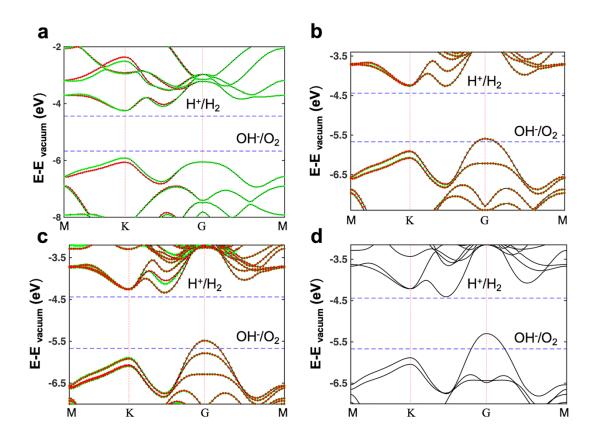
**Supplementary Figure 8** | PEC performance of  $MoS_x@GaN NWs/Si$  with different lengths of GaN NWs.



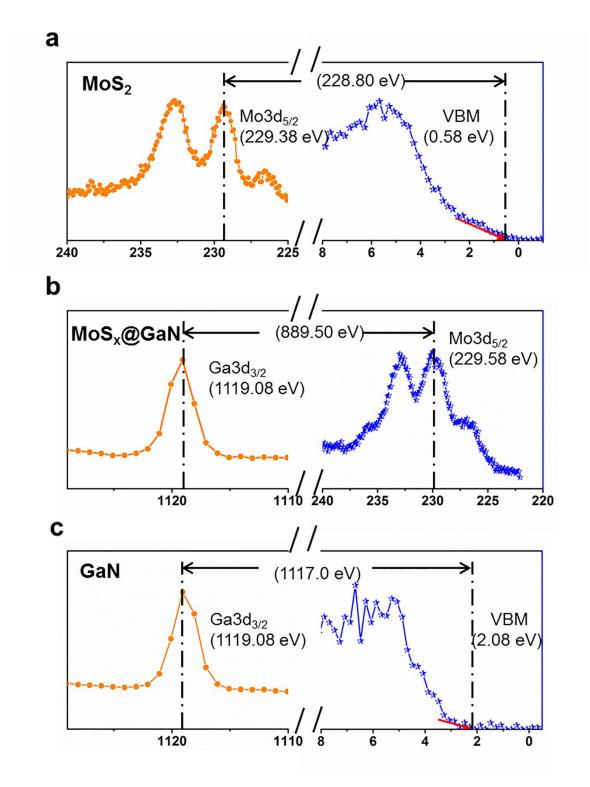
Supplementary Figure 9 | X-ray photoelectron spectrum. a  $MoS_x@GaN NWs/Si$  and b the core level spectra of Pt 4f before and after 10 hours reaction under standard one-sun irradiation in 0.5 mol L<sup>-1</sup> H<sub>2</sub>SO<sub>4</sub> aqueous solution.



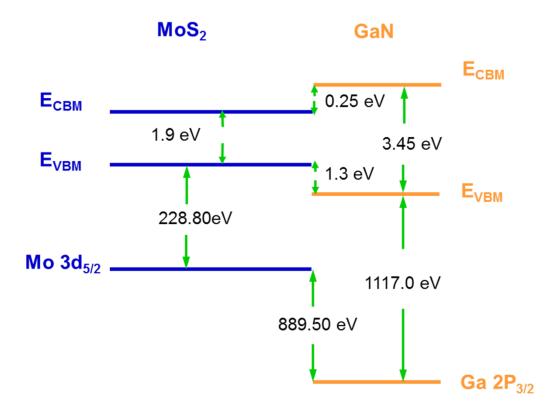
Supplementary Figure 10 | SEM image of  $MoS_x@GaN NWs/Si$  after 10 hours reaction under standard one-sun irradiation in 0.5 mol L<sup>-1</sup> H<sub>2</sub>SO<sub>4</sub> aqueous solution. Scale bar: 2 µm, inset 500 nm.



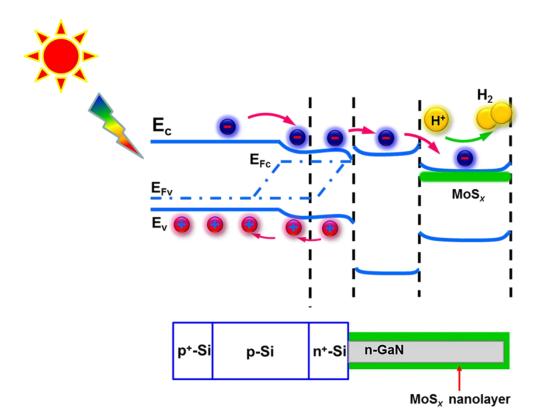
**Supplementary Figure 11** | Band structure of  $MoS_2$  with different thicknesses. **a**  $MoS_2$ -1L, **b**  $MoS_2$ -2L, **c**  $MoS_2$ -3L, **d**  $MoS_2$ -bulk. Spin-orbital coupling is taken into consideration for band structure calculations of few-layer  $MoS_2$ . In even-layer and bulk  $MoS_2$ , their inversion symmetry combined with time reversal leads to Kramers degeneracy, which means that no spin splitting exists. Oxidation-Reduction-Potential (ORP) is marked as  $OH^-/O_2$  and  $H^+/H_2$  with blue dashed line. This figure shows that regardless of the thickness of  $MoS_2$ , its conduction band minimum (CBM) remains at an optimal position referring to the reduction potential of  $H_2O$  splitting.



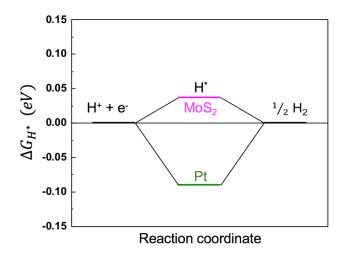
Supplementary Figure 12 | Core-level and valence band spectra based on XPS measurement. **a**  $MoS_2$ , **b**  $MoS_x@GaN$ , and **c** GaN.



Supplementary Figure 13 | The flat band alignment diagram of  $MoS_x@GaN$  based on XPS measurement.

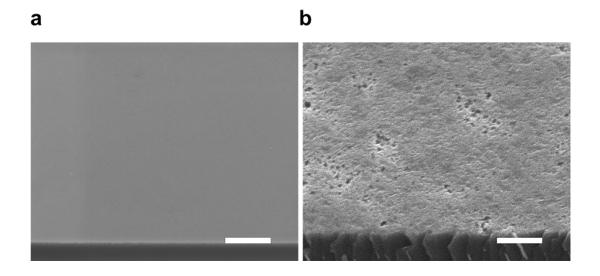


**Supplementary Figure 14** | Energy band diagram of  $MoS_x@GaN NWs/Si$  under illumination. Herein, both Si and GaN are heavily n-type doped, which can facilitate the electrons transfer from Si to GaN. Moreover, under irradiation, the abundant photogenerated electrons result in flat-band condition, which decreases the upward bending of surface energy and promotes the electron injection from n<sup>+</sup>-Si player to n-GaN at a small applied bias. The unique electronic interaction and outstanding geometric-matching structure between GaN and  $MoS_2$  further provides an ideal electron-migration channel for the electrons transfer to HER catalytic sites.



Supplementary Figure 15 | Free energy diagram of  $MoS_2$  for HER at equilibrium (U=0) relative

to SHE at pH = 0.



**Supplementary Figure 16** |  $45^{\circ}$ - titled SEM images. **a** bare planar n<sup>+</sup>-p junction Si and **b** MoS<sub>x</sub>/Si. Scale bar: 1 µm.